

L Number	Hits	Search Text	DB	Time stamp
1	1529	(dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)	USPAT	2004/03/17 15:52
2	89	((dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)) and (plug with (resin or polymer or photo\$1resist or photo\$1sensitive))	USPAT	2004/03/17 16:52
3	4	("6174796" "6319815" "6323121" "6380073").PN.	USPAT	2004/03/17 15:57
4	21	Chang-Weng.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2004/03/17 17:00
-	1529	(dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)	USPAT	2004/03/17 15:51
-	1345	((dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)) and (liner or conformal or sidewall or barrier)	USPAT	2004/03/17 09:14
-	736	((dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))	USPAT	2004/03/17 09:15
-	709	((dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via	USPAT	2004/03/17 09:15
-	390	((dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via) and (anisotropic\$4)	USPAT	2004/03/17 09:17
-	372	((dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via) and (anisotropic\$4)) and ((silicon adj nitride) or SiN or "Si.sub.3 N.sub.4" or carbide or oxynitride or SiON or TiN)	USPAT	2004/03/17 09:17
-	370	((dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via) and (anisotropic\$4)) and ((silicon adj nitride) or SiN or "Si.sub.3 N.sub.4" or carbide or oxynitride or SiON or TiN)) and @ay<=2002	USPAT	2004/03/17 09:18
-	342	((dual adj damascene) and (photo\$1resist or resist or photo\$1sensitive)) and (liner or conformal or sidewall or barrier)) and (etch\$1stop or (etch adj stop))) and via) and (anisotropic\$4)) and ((silicon adj nitride) or SiN or "Si.sub.3 N.sub.4" or carbide or oxynitride or SiON or TiN)) and @ay<=2001	USPAT	2004/03/17 11:36
-	1	6358842.pn.	USPAT	2004/03/17 11:35
-	11	("5536681" "5540812" "5759906" "5821168" "5976626" "5985762" "6024887" "6100181" "6100184" "6150723" "6194321").PN.	USPAT	2004/03/17 11:35

